

ISO 14606:2022-11 (E)

Surface chemical analysis - Sputter depth profiling - Optimization using layered systems as reference materials

Contents		Page
Foreword		iv
Introduction		v
1	Scope	1
2	Normative references	1
3	Terms and definitions	1
4	Symbols and abbreviated terms	1
5	Setting parameters for sputter depth profiling	2
5.1	General	2
5.2	Auger electron spectroscopy	3
5.3	X-ray photoelectron spectroscopy	3
5.4	Secondary ion mass spectrometry	4
6	Depth resolution at an ideally sharp interface in sputter depth profiles	4
6.1	Measurement of depth resolution	4
6.2	Average sputtering rate z_{av}	4
6.3	Depth resolution z	5
7	Procedures for optimization of parameter settings	5
7.1	Alignment of sputtered area with a smaller analysis area	5
7.1.1	General	5
7.1.2	AES	7
7.1.3	XPS with a small probe (e.g. monochromator)	7
7.1.4	XPS with a large area source (e.g. without monochromator)	7
7.1.5	SIMS	7
7.2	Optimization of parameter settings	8
Annex A (informative)	Factors influencing the depth resolution	9
Annex B (informative)	Typical single-layered systems as reference materials	12
Annex C (informative)	Typical multilayered systems used as reference materials	13
Annex D (informative)	Uses of multilayered systems	14
Bibliography		15